

SEMICONDUCTOR WASTE-GAS TREATING APPARATUS BEING FILTH
SEDIMENTATION- AND ETCHING-PROOF

ABSTRACT OF THE DISCLOSURE

A semiconductor waste-gas treating apparatus having the ability of
5 preventing sedimentation and etching of filth, the apparatus comprises a
header, a waste gas treating trough and an annular guide. The apparatus
takes advantage of the function that a header generates flame of high
temperature to catalytically decompose waste gas, and by cooperation
between an annular guide and a waste gas treating trough, an annular water
10 wall can be formed on the inner wall a waste gas reacting room to isolate and
prevent powder and erosive material from contact with the wall of the
reacting room; thereby, the phenomenon of sedimentation and etching of filth
in the semiconductor waste-gas treating trough can be eliminated.

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